

VAKSiS

R&D AND ENGINEERING

MIDAS_m



PRODUCT INFORMATION

MIDAS_m series are the smallest member of the Vaksis MIDAS COATING SYSTEMS platforms. This series are composed of prismatic vacuum chambers and involve the techniques and combinations below:

CONFIGURATION MATRIX

Techniques	Magnetron Sputtering (MS)	Thermal Evaporation (Th E)	Electron Beam (e-Beam)	Organic and Metal Evaporation (OLED/OPV)	Multi Tech.
MIDAS _m	✓	✓	✓	✓	MS, Th E, e-Beam, OLED/OPV

TECHNICAL SPECIFICATIONS

Ultimate Vacuum Pressure $\leq 5 \times 10^{-7}$ Torr
 Substrate Size max. 4" diameter
 Substrate Heating max. 800°C
 Substrate Rotation 3-30 rpm
 Cooling Where necessary
 Deposition Mode Upward
 Thickness Measurement In-situ measurement with Quartz X-tal Oscillator
 Control Fully Automatic

POWER SOURCES

- DC and/or RF Power Supply for Sputtering Magnetron Source
- Effusion Cell A.C. Power Supply for Metal and/or Organic Evaporation Sources
- High-Current Low-Voltage A.C. Power Supply for Resistive Thermal Evaporation Source
- Power Supply for Electron Beam Evaporation Source

SOFTWARE

System operation by user-friendly software. It is not only the automation and control software but also coating management software which allows the user design his/her specific coating experiments, examine the process parameters used in the past, and use the recipes/coatings developed in the past without hustle.

Human and machine safeties are prime importance in the operations performed by the software.

A graphical user interface will allow the user to see the status of the system during operations.